

→ Diffusion Approximation

* Consider transport equation for h^+ s

$$J_p = p q \mu_p E - q D_p \frac{\partial p}{\partial x}$$

$$\text{If } \left| q D_p \frac{\partial p}{\partial x} \right| \gg |p q \mu_p E|$$

$$J_p \approx -q D_p \frac{\partial p}{\partial x}$$

Diffusion approximation for h^+ s
in an n-type semiconductor

* Consider transport equation for e^- s

$$J_n = n q \mu_n E + q D_n \frac{\partial n}{\partial x}$$

$$\text{If } \left| q D_n \frac{\partial n}{\partial x} \right| \gg |n q \mu_n E|$$

$$J_n \approx q D_n \frac{\partial n}{\partial x}$$

Diffusion approximation for e^- s
in p-type semiconductor

→ The drift component depends on carrier concentration and applied electric field.

→ But the diffusion component depends only on concentration gradient.

→ There is a possibility that the carrier concentration is small, but concentration gradient is large, where the diffusion approximation is valid.

The diffusion approximation is applicable for minority carriers.

The consequences of diffusion approximation



→ Consider continuity equation for holes

$$\frac{\partial \delta p}{\partial t} = -\frac{1}{q} \frac{\partial J_p}{\partial x} + G' - \frac{\delta p}{\tau}$$

$$J_p = +q \mu_p E - q D_p \frac{\partial p}{\partial x}$$

Under diffusion approximation $\Rightarrow J_p \simeq -q D_p \frac{\partial p}{\partial x}$

$$\frac{\partial \delta p}{\partial t} = D_p \frac{\partial^2 p}{\partial x^2} + G' - \frac{\delta p}{\tau}$$

Under steady state condition $\rightarrow \frac{\partial}{\partial t} = 0$

$$0 = D_p \frac{\partial^2 p}{\partial x^2} + G' - \frac{\delta p}{\tau}$$

$$p = p_0 + \delta p, p_0 \text{ is uniform} \Rightarrow \frac{\partial p}{\partial x} = \frac{\partial \delta p}{\partial x}$$

$$0 = D_p \frac{\partial^2 (\delta p)}{\partial x^2} + G' - \frac{\delta p}{\tau}$$

$$\frac{\partial^2 (\delta p)}{\partial x^2} = \frac{1}{D_p} \left(\frac{\delta p}{\tau} - G' \right) = \frac{\delta p - G' \tau}{D_p \tau}$$



→ If G' is uniform (G' is not varying with distance or uniform volume generation)

$$\frac{\partial^2 (\delta p - G' \tau)}{\partial x^2} = \frac{(\delta p - G' \tau)}{D_p \tau}$$

τ - Average life time of excess carriers

(m)
Average life time of minority carriers

$$\frac{\partial^2 (\delta p - G' \tau_p)}{\partial x^2} = \frac{(\delta p - G' \tau_p)}{D_p \tau_p}$$



$$L_p^2 = D_p \tau_p$$

$$\Rightarrow L_p = \sqrt{D_p \tau_p}$$

Diffusion length of the holes

$$L_n = \sqrt{D_n \tau_n}$$

Diffusion length of the electrons

$$L = \sqrt{D \tau}$$



$$p = p_0 + \delta p = p_0 + \Delta p e^{-x/L_p}$$

$$\Delta p = \delta p|_{x=0}$$

$$n = n_0 + \delta n = n_0 + \Delta n e^{-x/L_n}$$

$$\Delta n = \delta n|_{x=0}$$

→ Under low level injection assumption, the injected minority carrier current for an extrinsic semiconductor is essentially the

(a) diffusion current

(b) drift current

(c) recombination current

(d) induced current

→ Electron mobility and life time in a semiconductor at room temperature are respectively $0.36 \text{ m}^2/\text{V-s}$ and $340 \mu\text{s}$. The diffusion length is $\underline{\quad \mu\text{m} \quad}$



$$L_n = \sqrt{D_n \tau_n}$$

$$\frac{D_n}{\mu_n} = V_T$$

$$D_n = \mu_n V_T$$

$$L_n = \underline{\underline{1.78 \text{ mm}}}$$

→ In a very long p-type Si bar with cross-sectional area 0.5 cm^2 and $N_A = 10^{17} / \text{cm}^3$, we inject holes such that the steady state excess hole concentration is $\Delta p = 5 \times 10^{16} / \text{cm}^3$ at $x=0$.

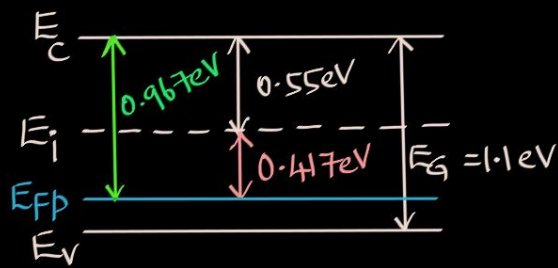


(1) What is the steady state separation between E_{fp} and E_c at $x = 1000 \text{ \AA}$?

(2) What is the hole current there?

(3) How much is the excess stored hole charge?

Assume that $\mu_p = 500 \text{ cm}^2/\text{V-s}$ and $\tau_p = 10^{-10} \text{ s}$, $E_g = 1.1 \text{ eV}$ and $n_i = 1.5 \times 10^{10} / \text{cm}^3$.



$$(1) E_i - E_{fp} = kT \ln\left(\frac{p}{n_i}\right)$$

$$p = p_0 + \Delta p e^{-x/L_p}$$

$$\underline{E_c - E_{fp} = 0.967 \text{ eV}}$$

$$L_p = \sqrt{D_p \tau_p}$$

$$D_p = \mu_p V_T = 13 \text{ cm}^2/\text{s}$$

$$L_p = 3.6 \times 10^{-5} \text{ cm}$$

$$1000 \text{ \AA} = 1000 \times 10^{-8} \text{ cm} = 10^{-5} \text{ cm}$$

$$p = 10^{17} + 5 \times 10^{16} e^{-10^{-5} / 3.6 \times 10^{-5}} = 1.377 \times 10^{17} / \text{cm}^3$$

$$E_i - E_{fp} = 0.026 \times \ln\left(\frac{1.377 \times 10^{17}}{1.5 \times 10^{10}}\right) = 0.417 \text{ eV}$$

$$(2) I_p = ? \quad x = 1000 \text{ \AA}$$

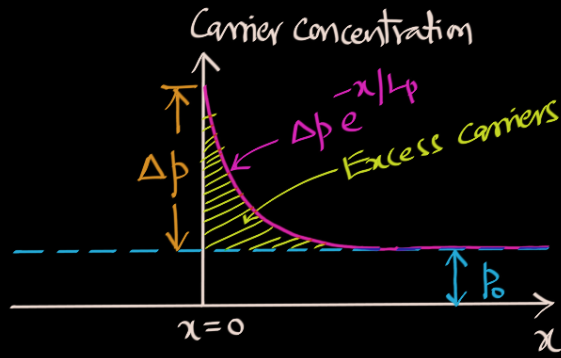
$$J_p = -q D_p \frac{\partial p}{\partial x} \Rightarrow I_p = -A q D_p \frac{\partial p}{\partial x}$$

$$I_p = -A q D_p \frac{\partial}{\partial x} (p_0 + \Delta p e^{-x/L_p}) = \frac{A q D_p}{L_p} \Delta p e^{-x/L_p}$$

$$= \frac{0.5 \times 1.6 \times 10^{-19} \times 13}{3.6 \times 10^{-5}} \times 5 \times 10^{16} e^{-10^{-5} / 3.6 \times 10^{-5}}$$

$$= 1.09 \times 10^3 \text{ A}$$

(3)



$$Q_p = \int_0^{\infty} A q \Delta p e^{-x/L_p} dx$$

$$= A q \Delta p_0 \int_0^{\infty} e^{-x/L_p} dx$$

$$Q_p = A q \Delta p e^{-x/L_p} \Big|_0^{\infty} (-L_p)$$

$$Q_p = A q \Delta p L_p$$

$$Q_p = 0.5 \times 1.6 \times 10^{-19} \times 5 \times 10^{16} \times 3.6 \times 10^{-5}$$

$$Q_p = 144 \text{ nC}$$



Space charge Neutrality

It means that " $\rho = 0$ "

Consider Gauss law $\Rightarrow \frac{\partial E}{\partial x} = \frac{\rho}{\epsilon}$

$$\boxed{\frac{\partial E}{\partial x} = 0} \quad \begin{array}{l} E \text{ is constant} \\ \text{w.r.t } x, \text{ where } \rho = 0 \end{array}$$

* Quasi-neutrality $\rightarrow \rho \simeq 0, \delta p \simeq \delta n$

$$\boxed{\delta n, \delta p \gg |\delta n - \delta p| \Rightarrow \rho \simeq 0}$$



* Depletion approximation

→ Consider space charge

$$\begin{aligned}\rho &= q(p + N_D^+ - n - N_A^-) \\ &= q(p - n + N_D^+ - N_A^-)\end{aligned}$$

Id $|p - n| \ll |N_D^+ - N_A^-|$

$$\boxed{\rho \simeq q(N_D^+ - N_A^-)} \text{ Depletion approximation}$$

* Debye Length (L_D)

→ Consider an n-type semiconductor

$$\rho = q(p - n + N_D^+ - N_A^-)$$

Under depletion approximation

$$\rho \simeq q(N_D^+ - \overset{\circ}{N_A^-})$$

$$\rho \simeq qN_D^+$$

Consider the Gauss law

$$\frac{\partial E}{\partial x} = \frac{\rho}{\epsilon}$$

$$\frac{\partial E}{\partial x} = \frac{qN_D^+}{\epsilon}$$

$$\frac{\partial^2 \psi}{\partial x^2} = -\frac{qN_D^+}{\epsilon} \quad \because E = -\frac{\partial \psi}{\partial x}$$

$$\frac{\partial^2 \psi}{\partial x^2} = -\left(\frac{qN_D^+}{\epsilon V_T}\right) V_T$$

$$\frac{1}{L_D^2} = \frac{qN_D^+}{\epsilon V_T}$$

$$L_D = \sqrt{\frac{\epsilon V_T}{q N_D^+}}$$

Debye length

L_D depends on doping

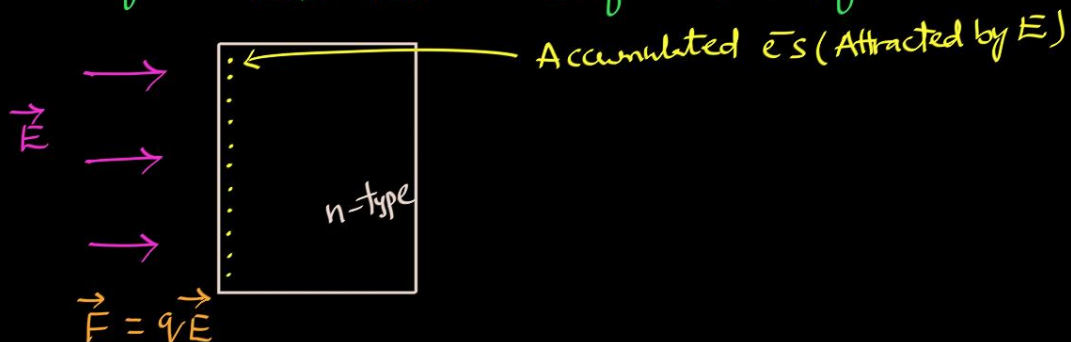


$\frac{\partial^2 \psi}{\partial x^2} = -\frac{V_T}{L_D^2} \Rightarrow$ The Debye length describes the variation of the potential with distance in space charge region (or) depletion region

* L_n and L_p describes variation of carrier concentration with distance.

Charge sheet Approximation

* This approximation is usually used to describe free carriers near the surface (or) interface.



* The carrier concentration is very high close to the surface and decreases very rapidly when moving away from the surface within a small distance. So it can be considered as sheet of charge.

* This approximation is used in MOS capacitors

Gradual channel Approximation

* It is used to convert a 2D situation into 1D situation approximately.

* This approximation is used in MOSFETs

Consider Gauss law in 2D

$$\frac{\partial E_x}{\partial x} + \frac{\partial E_y}{\partial y} = \frac{\rho}{\epsilon}$$

$$\frac{\partial E_x}{\partial x} \approx \frac{\rho}{\epsilon} - 1D$$

If $\frac{\partial E_x}{\partial x} \gg \frac{\partial E_y}{\partial y}$ then

Procedure for Device Analysis – Summary



Step(1) Same set of approximations may not hold over the entire device volume. Hence, partition the device into different regions.

Step(2) Analyse each region using a suitable set of approximations and boundary conditions to obtain n, p, J_n, J_p and E in that region. Approximations for different regions may be different.

Step(3) Combine the information regarding n, p, J_n, J_p and E obtained in different regions, ensuring "continuity of these parameters" across boundaries separating the regions to obtain the complete picture.



Basic Device Building Blocks

(1) Metal - Semiconductor Interface



Metal	Semiconductor
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(Schottky barrier)

→ Rectifying contacts - Allows current only in one direction

→ Ohmic contacts (Non-rectifying contacts) - Allows current in both the directions with negligible voltage drop.

(2) pn Junction



p-type Semiconductor	n-type Semiconductor
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* BJT → pnp, npn

* Thyristor → pnpn

(3) Heterojunction

Ex:

GaAs

AlAs



These are key components in high-speed and optoelectronic devices



(4) Metal-Oxide-Semiconductor structure



* MOS Capacitor / Junction / Diode

* MOSFET

pn Junction



- Equilibrium (zero bias or open circuit)
- Ideal V-I characteristics
- Variation of V-I characteristics with temperature
- Diode resistance
- Diode equivalent circuits
- Breakdown mechanisms
- Junction capacitance
- Small signal characteristics
- Switching times of the diode

Equilibrium Analysis

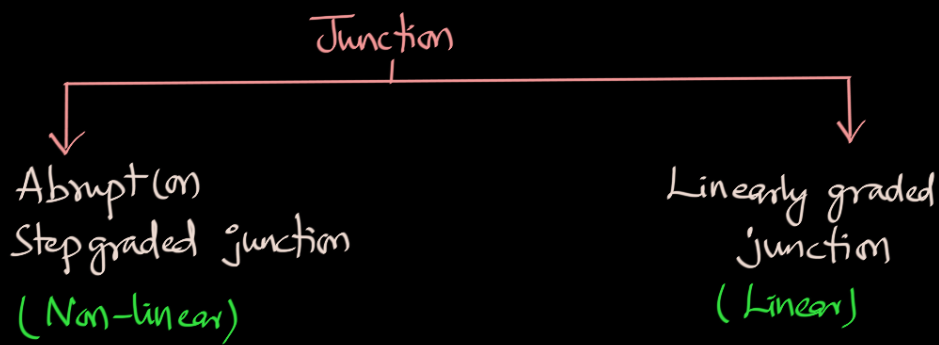


Qualitative

Quantitative

n, p, J_n, J_p and E

- * Width of the depletion region
- * Built-in potential (or) contact potential
- * Maximum electric field
- * Charge stored in the depletion region



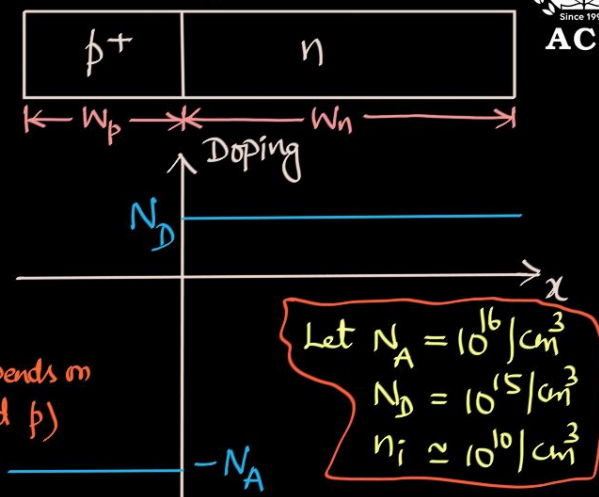
Equilibrium (zero bias or open circuit) - Qualitative Analysis

* Abrupt and uniform junction

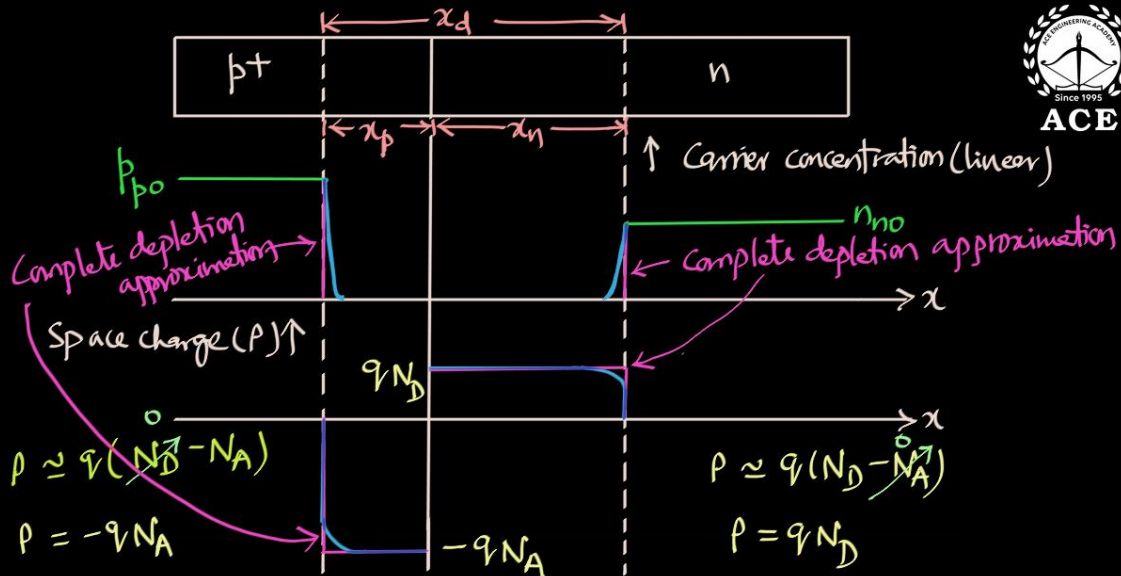
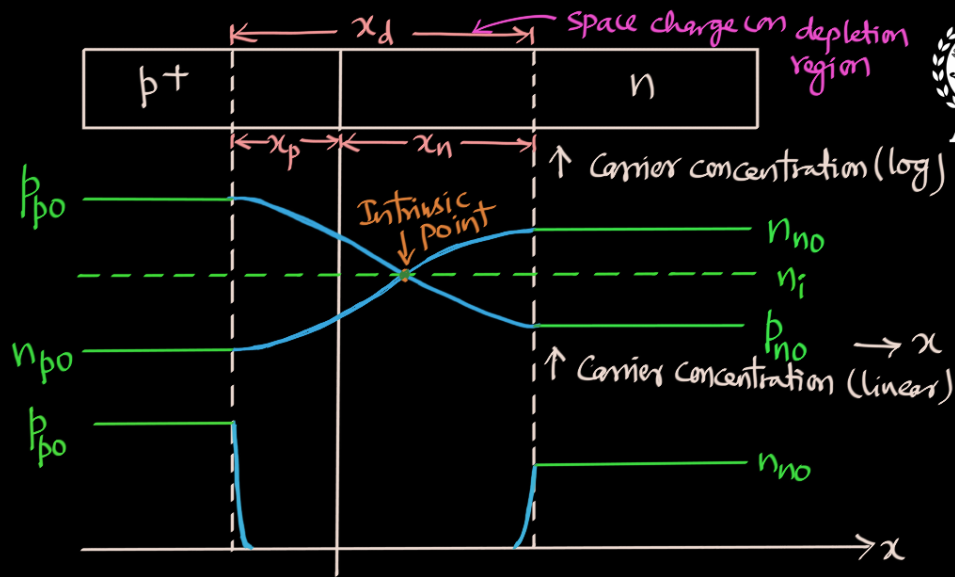
$$L_n \ll W_p$$

$$L_p \ll W_n$$

→ n_i, β, J_n, J_p and E (depends on n and β)



n, p



→ Consider space charge $\rho = q(p - n + N_D^+ - N_A^-)$

Let all the impurities are ionized

$$\rho = q(p - n + N_D - N_A)$$

Apply complete depletion approximation

$$p - n = 0$$

$$|p - n| \ll |N_D - N_A| \Rightarrow \rho \approx q(N_D - N_A)$$

Depletion approximation